

Resource Summary Report

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Oxford: PlasmaPro 800 RIE Plasma Technology

RRID:SCR_020398

Type: Tool

Proper Citation

Oxford: PlasmaPro 800 RIE Plasma Technology (RRID:SCR_020398)

Resource Information

URL: <https://plasma.oxinst.com/products/rie/plasmapro-800>

Proper Citation: Oxford: PlasmaPro 800 RIE Plasma Technology (RRID:SCR_020398)

Description: PlasmaPro 800 offers solution for reactive ion etching processes on large wafer batches and 300mm wafers, in compact footprint, open loading system. Large wafer platen allows for production scale batch processing and 300mm wafer handling.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

Availability: Commercially available

Resource Name: Oxford: PlasmaPro 800 RIE Plasma Technology

Resource ID: SCR_020398

Alternate IDs: Model_Number_800_RIE

Record Creation Time: 20220129T080350+0000

Record Last Update: 20260801T190649+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 800 RIE Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 800 RIE Plasma Technology.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.